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(21) International Application Number: PCT/SG97/00051 (22) International Filing Date: 3 October 1997 (03.10.97) (30) Priority Data: 9/226923 25 August 1997 (25.08.97) JP (71) Applicant (for all designated States except US): UNIQUE TECHNOLOGY INTERNATIONAL PTE. LTD. [SG/SG]; Block 21 Kallang Avenue, #04-165 Kallang Basin Industrial Estate, Singapore 339412 (SG). (72) Inventors; and (75) Inventors/Applicants (for US only): TANI, Kazunori [JP/JP]; International Business Park #03-03, Singapore 609915 (SG). KAWACHI, Kohichi [JP/JP]; Kanbo Create Co., Ltd., 6-9, Bakurumachi 1-chome, Chuo-ku, Osaka (JP). (74) Agent: HAQ, Murgiana; Haq & Namazie Partnership, Robinson Road Post Office, P.O. Box 765, Singapore 901515 (SG).		(81) Designated States: JP, KR, SG, US. Published With international search report.
(54) Title: COMBINATION ELECTROLYTIC POLISHING AND POLISHING AND TEXTURING MACHINE AND THE COMBINATION ELECTROLYTIC POLISHING AND POLISHING AND TEXTURING TAPE USED IN THE SAID MACHINE		
(57) Abstract Objective: to provide a combination electrolytic polishing and polishing and grinding machine and processing tape which will enable the formation on the surface of hard disks uniform, accurate texturing without abnormal protrusions. Composition: a polishing and texturing machine and processing tape in which a layer which can hold polishing grains is formed with flocking or foam resin on one surface of tape-shaped backing, such as synthetic resin film or woven material or non-woven cloth, and electrolytic solution into which polishing grains have been dispersed is supplied to this tape to conduct polishing or texturing of the hard disk board, at the same time as which a voltage is applied between the electrode established close to the surface being processed and the disk board to enable electrolytic polishing. Effect: simultaneous mechanical processing and electrolytic polishing enables the efficient provision of hard disks in one-stage processing with surface properties equal, or superior to those produced in two-stage processing. 10 Electrolytic solution 1 Texturing tape 9 Polishing grains 8 Pressure roller (cathode) 7 Disk board		